## **SECTION II. (AMENDMENTS TO THE CLAIMS)**

A listing of claims 1-60 of the present application, as amended/added herein with markings showing changes made, is provided below:

1-28. (Cancelled).

29-32. (Cancelled).

33. (Currently amended) The A layered structure of claim 29 comprising:

a substrate having an upper surface of single crystalline Si, and

a layer of SiC over said upper surface,

said layer of SiC and said upper surface of single crystalline Si define an interface having an abrupt change in C concentration of more than 1 x 10<sup>18</sup> atoms/cc, wherein the oxygen in said layer of SiC is less than 1 x 10<sup>17</sup> atoms/cc, and

wherein said layer of SiC includes a p-type dopant in the range from about  $1 \times 10^{18}$  to about  $1 \times 10^{21}$  atoms/cc and wherein said SiC layer of SiC with said p-type dopant can withstand furnace anneals to temperatures of 850° C and rapid thermal anneal temperatures to 1000° C.

34. (Currently amended) The A layered structure of claim 29 comprising:

a substrate having an upper surface of single crystalline Si, and

a layer of SiC over said upper surface,

said layer of SiC and said upper surface of single crystalline Si define an interface having an abrupt change in C concentration of more than  $1 \times 10^{18}$  atoms/cc, wherein the oxygen in said layer of SiC layer is less than  $1 \times 10^{17}$  atoms/cc, and

wherein said layer of SiC includes a n-type dopant in the range from about 1 x  $10^{18}$  to about 1 x  $10^{21}$  atoms/cc.

35. (Currently amended) The layered structure of claim 33 further including a layer of Si over said layer of p-type doped SiC, said p-type doped SiC layer and said Si layer

define an interface having an abrupt change in C concentration above  $1 \times 10^{18}$  atoms/cc over a layer thickness in the range from about 6 A to about 60 A and wherein the oxygen in said Si layer is less than  $1 \times 10^{17}$  atoms/cc.

- 36. (Currently amended) The layered structure of claim 35 wherein said interface defined by said p-type doped SiC layer and said Si layer has an abrupt change in p-dopant concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 Å to about 60 Å.
- 37. (Currently amended) The layered structure of claim 34 further including a layer of Si over said layer of n-type doped SiC, said n-type doped SiC layer and said Si layer define an interface having an abrupt change in C concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 Å to about 60 Å and wherein the oxygen in said Si layer is less than 1 x 10<sup>17</sup> atoms/cc.
- 38. (Currently amended) The layered structure of claim 37 wherein said interface defined by said n-type doped SiC layer and said Si layer has an abrupt change in dopant concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 Å to about 60 Å.
- 39. (Currently amended) The layered structure of claim 29 further including a layer of SiGe over said layer of SiC, said SiC layer and said SiGe layer of SiGe define an interface having an abrupt change in C concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 A to about 60 A and wherein the oxygen in said SiGe layer of Sige is less than 1 x 10<sup>17</sup> atoms/cc.
- 40. (Currently amended) The layered structure of claim 33 further including a layer of SiGe over said layer of p-type doped SiC, said p-type doped SiC layer and said SiGe layer of SiGe define an interface having an abrupt change in C concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 A to about 60 A and wherein the oxygen in said SiGe layer of SiC is less than 1 x 10 17 atoms/cc.

41. (Currently amended) The layered structure of claim 34 further including a layer of SiGe over said layer of n-type doped SiC, said n-type doped SiC layer and said SiGe layer of SiGe define an interface having an abrupt change in C concentration above 1 x 10<sup>18</sup> atoms/cc over a layer thickness in the range from about 6 A to about 60 A and wherein the oxygen in said SiGe layer of SiGe is less than 1 x 10<sup>17</sup> atoms/cc.

42-60. (Cancelled).